

Examples of the Equipment for MCP Applications

Illustrative Field,etc	Mass spectroscopy			Semiconductor inspection			Surface analysis		
Input	Ion	Time-of-flight mass spectroscopy (TOF-MS) (MALDI)	Ion	Time-of-flight mass spectroscopy (TOF-MS) (LC-MS)	Ion	Time-of-flight mass spectroscopy (TOF-MS) (GC-MS)	Ion	Quadrupole mass spectroscopy (Q-MS)	Ion
	Ion	Double focusing mass spectroscopy (Sector-MS)	Ion	Gas or liquidchromatographic mass spectroscopy (GC/LC-MS)	Ion	Inductive-coupled plasma mass spectroscopy (ICP-MS)	Ion	Secondary ion mass spectroscopy (SIMS)	Ion
	Ion	Scanning electron microscope (SEM)	Electron	Scanning ion microscope (SIM)	Electron, Ion	Electron beam measuring system (EBMS)	Electron, Ion	Electron or ion beam lithography	Electron
	Electron	Mask aligner	Electron, Ion	FIB system	Electron	Auger electron spectroscopy (AES)	Ion	Ion scattering spectroscopy (ISS)	Electron
									Electron spectroscopy for chemical analysis (ESCA)
							Ion	Rutherford backscattering spectroscopy (RBS)	UV
							UV	Vacuum UV spectroscopy (VUVS)	X-ray*
							X-ray*	Soft X-ray spectroscopy (SXS)	Electron
								Reflection medium energy electron diffraction (RMED)	Electron
								Low energy electron diffraction (LEED)	Ion
								Field ion microscope (FIM)	Electron
								Transmission electron microscope (TEM)	X-ray*
								Soft X-ray microscope (SXM)	Positron
								Positron detector	

*Note: The applications of X-ray input are covered by the exemption “1. Lead, cadmium and mercury in detectors for ionising radiation.” in Annex IV of 2011/65/EU